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(54) **Chemical mechanical polishing pad**

(57) The polishing pad is for polishing patterned semiconductor substrates. The pad includes a polymeric matrix and hollow polymeric particles within the polymeric matrix. The polymeric matrix is a polyurethane reaction product of a curative agent and an isocyanate-terminated polytetramethylene ether glycol at an NH₂ to NCO stoichiometric ratio of 80 to 97 percent. The isocyanate-terminated polytetramethylene ether glycol has an unreacted NCO range of 8.75 to 9.05 weight percent. The hollow polymeric particles having an average diameter of 2 to 50 μm and a wt%_b and density_b of constituents forming the polishing pad as follows:

$$\frac{wt\%_a * density_b}{density_a} = wt\%_b$$

where density_a equals an average density of 60 g/l, where density_b is an average density of 5 g/l to 500 g/l, where wt%_a is 3.25 to 4.25 wt%. The polishing pad has a porosity of 30 to 60 percent by volume; and a closed cell structure within the polymeric matrix forms a continuous network surrounding the closed cell structure.



EUROPEAN SEARCH REPORT

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EP 09 15 4680

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| | | | TECHNICAL FIELDS SEARCHED (IPC) |
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| The present search report has been drawn up for all claims | | | |
| 1 | Place of search | Date of completion of the search | Examiner |
| | Munich | 6 May 2013 | Gelder, Klaus |
| CATEGORY OF CITED DOCUMENTS | | T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document | |
| X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document | | | |

**ANNEX TO THE EUROPEAN SEARCH REPORT
ON EUROPEAN PATENT APPLICATION NO.**

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